

EAST

103

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--|-------------------|------------------|---------|------------------|
| L1 | 3627 | ((427/8) or (427/420) or (427/421.1) or (427/424) or (427/427.2) or (427/427.3) or (427/427.4) or (427/427.6)).CCLS. | US-PGPUB; USPAT | OR | OFF | 2005/07/19 07:29 |
| L2 | 126 | 1 and @pd>"20050215" | US-PGPUB; USPAT | OR | ON | 2005/07/19 07:22 |
| L3 | 44 | 2 and (disk or disc or wafer) | US-PGPUB; USPAT | OR | ON | 2005/07/19 07:29 |
| L4 | 2 | jp-10284397-\$.did. | EPO; JPO; DERWENT | OR | ON | 2005/07/19 07:24 |
| L5 | 0 | jp-109320950-\$.did. | EPO; JPO; DERWENT | OR | ON | 2005/07/19 07:25 |
| L6 | 2 | jp-09320950-\$.did. | EPO; JPO; DERWENT | OR | ON | 2005/07/19 07:25 |
| L7 | 1 | jp-07169684-\$.did. | EPO; JPO; DERWENT | OR | ON | 2005/07/19 07:26 |
| L8 | 1398 | wafer and (resist or photoresist) and (nozzle) | EPO; JPO; DERWENT | OR | ON | 2005/07/19 07:27 |
| L9 | 2 | 8 and (edge near3 distance) | EPO; JPO; DERWENT | OR | ON | 2005/07/19 07:27 |
| L10 | 20 | wafer and (resist or photoresist) and (edge near3 distance) | EPO; JPO; DERWENT | OR | ON | 2005/07/19 07:28 |
| L11 | 1167 | (427/240).CCLS. | US-PGPUB; USPAT | OR | OFF | 2005/07/19 07:29 |
| L12 | 23 | 11 and (edge near3 distance) | US-PGPUB; USPAT | OR | ON | 2005/07/19 07:30 |
| L13 | 82 | 1 and (edge near3 distance) | US-PGPUB; USPAT | OR | ON | 2005/07/19 07:30 |
| L14 | 1 | 1 and ((edge near3 distance) with (wafer or disk or disc)) | US-PGPUB; USPAT | OR | ON | 2005/07/19 07:31 |
| L15 | 10 | 1 and ((edge near3 distance) with (substrate)) | US-PGPUB; USPAT | OR | ON | 2005/07/19 07:31 |